

7th Semester Regular / Back Examination 2017-18
Surface Engineering
BRANCH: METTA, MME
Time: 3 Hours
Max Marks: 70
Q.CODE: B438

Answer Question No.1 which is compulsory and any five from the rest.
The figures in the right hand margin indicate marks.

- Q1 Answer the following questions: (2 x 10)**
- Why iron and chromium cannot be deposited as an alloy under normal condition?
 - What is the scope of surface engineering in ceramics and polymers?
 - What is the difference between carbo – nitriding and Nitro – carburizing?
 - Write down the CVD reactions for the deposition of Si and SiO₂?
 - In between the APCVD and LPCVD process, which one is the mass transfer controlled and which one is the reaction rate controlled and why ?
 - Briefly explain surface treatment of a metal bi ion implantation?
 - What are the advantages of Cu deposited by electrochemical method to a Cu deposited by other methods?
 - Write down the advantages of cold wall reactor over hot wall reactor in a CVD process?
 - For deposition of TiN by sputter coating method from a Ti target material which gas should be used as a plasma generating gas and why?
 - If an aircraft flies through a dust cloud which type of wear process generally occurs and how can you improve wear resistance of the affected part?
- Q2 a) Explain chromate coating with its reactions. Also write its applications? (5)**
b) What do you understand by phosphating? Also describe the general phosphating reaction for coating formation? (5)
- Q3 a) What do you understand by electroplating? What is the purpose of electroplating? (5)**
b) What should be the various characteristics of an electrolytic solution? (5)
- Q4 a) Explain electroplating of Nickel by Watt's solution and role of different constituents? (5)**
b) Explain electro-deposition of Tin using both methods(acid and alkaline)? (5)
- Q5 a) Write plating solution and operating condition of cyanide bath for copper plating?What are the troubles with cyanide bath for copper plating? (5)**
b) Explain chemical vapour deposition technique. What are the various chemical reactions in CVD? (5)
- Q6 a) Give a comparison between LCVD (laser CVD & PECVD(plasma enhanced CVD)? Write a short note on laser CVD. (5)**
b) What is sputtering? Write its types. Explain any one method of sputtering? (5)
- Q7 a) Explain ion implantation process with its collision cascade process? Explain any one method of measuring coating thickness? (5)**
b) What do you understand by PVD? What are the various stages in growth of film formation by PVD? (5)
- Q8 Write short notes on any TWO : (5x2)**
- Electro - less Plating
 - Thermal Evaporation
 - Carbo - nitriding